

ABSTRACT

SEMICONDUCTOR STRUCTURE AND FORMING METHOD THEREOF

The present disclosure relates to a semiconductor structure and a forming method thereof. The semiconductor structure includes: a substrate; a capacitive structure, located on a top surface of the substrate and including a plurality of capacitors arranged in an array along a first direction and a second direction, wherein the first direction and the second direction are each parallel to the top surface of the substrate, and the first direction intersects with the second direction; a transistor structure, located above the capacitive structure and including a plurality of active pillars and a plurality of word lines, wherein the active pillar is electrically connected to the capacitor, and the word line extends along the second direction and continuously cover the active pillars arranged at intervals along the second direction; and a bit line structure, located above the transistor structure and including a plurality of bit lines, wherein the bit line extends along the first direction and are electrically connected to the active pillars arranged at intervals along the first direction. The present disclosure reduces the process difficulty and helps improve the performance of the semiconductor structure.

Figure 1